

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	154	damascene and adhesion adj film	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 11:48
L4	3	damascene and adhesion adj film same cap adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:00
L5	48	damascene and clean near2 process\$3 near2 chamber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:00
L6	42	L5 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:40
L7	1	@pn="6071809"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:41
L8	1	@pn="6787875"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:42
L9	1	@pn="6479380"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:42
L10	1	@pn="6599830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:42

L11	1	@pn="6605874"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:43
L12	1	@pn="6759321"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:50
L13	458	438/618.ccor.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:54
L14	422	L13 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:54
L15	761	438/637.ccor.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:54
L16	655	L15 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 13:54
S1	1	@pn="6605874"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 10:44
S2	1	@pn="6599830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 10:45

S3	24	damascene and third adj hard adj mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 10:45
S4	14	S3 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 11:24
S5	5	S4 and silk	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 11:24
S6	209	damascene and hard adj mask same (TaN WN (tantalum adj nitride) (tungsten adj nitride))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 16:44
S7	178	S6 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 16:44
S8	82	damascene and hard adj mask near12 (TaN WN (tantalum adj nitride) (tungsten adj nitride))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 16:44
S9	68	S8 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/28 17:23
S10	2	"20050079706"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 09:48

S11	0	damascene and (hardmask (hard adj mask)) near8 nitrogen adj silicon adj carbide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:54
S12	0	(hardmask (hard adj mask)) near8 nitrogen adj silicon adj carbide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:52
S13	0	(hardmask (hard adj mask)) same nitrogen adj silicon adj carbide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:52
S14	1	(hardmask (hard adj mask)) same N adj SiC	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:53
S15	100	"nitrogen doped silicon carbide"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:53
S16	56	S15 and damascene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:53
S17	14	S16 and hard adj mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:53
S18	15	damascene and (hardmask (hard adj mask)) near8 SiCN	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:54

S19	11	S18 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 08:54
S20	177	damascene and ((third three) adj (mask hardmask (hard adj mask)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 09:50
S21	113	S20 and @ad<"20031014"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 11:48